

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1980	semiconductor and gate and source and drain and silicide and (silicid\$3 adj (gate or electrode))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/07 08:58
L2	867	semiconductor and (polysilicon adj (gate or electrode)) and source and drain and silicide and (silicid\$3 adj (gate or electrode))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/07 08:58
L3	867	semiconductor and (polysilicon adj (gate or electrode)) and source and drain and silicide and (silicid\$3 adj (gate or electrode))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/07 08:59
L4	739	semiconductor and (polysilicon adj (gate or electrode)) and source and drain and silicide and (silicid\$3 adj (gate or electrode)) and @ad<="20040326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/07 09:09
L5	175	semiconductor and (polysilicon adj (gate or electrode)) and source and drain and silicide and (silicid\$3 adj (gate or electrode)) and @ad<="20040326" and polycide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/07 09:10
S6	0	(polysilicon adj gate adj electrode) with (protect\$ adj (layer or film)) with (wet adj etch\$6)	US-PGPUB; USPAT	OR	ON	2006/09/07 08:56
S7	114	(polysilicon adj gate adj electrode) and (protect\$ adj (layer or film)) and (wet adj etch\$6)	US-PGPUB; USPAT	OR	ON	2005/06/07 08:54
S8	2	(polysilicon adj gate adj electrode) same (protect\$ adj (layer or film)) same (wet adj etch\$6)	US-PGPUB; USPAT	OR	ON	2005/06/07 09:10
S9	0	438/257,583.ccls. and (polysilicon adj gate adj electrode) same (protect\$ adj (layer or film)) same (wet adj etch\$6)	US-PGPUB; USPAT	OR	ON	2005/06/07 09:10
S10	0	438/257,583.ccls. and (polysilicon adj gate adj electrode) same (protect\$ adj (layer or film)) same (wet adj etch\$6)	US-PGPUB; USPAT	OR	ON	2006/09/07 08:57

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S11	2	438/257,583.ccls. and (polysilicon adj gate adj electrode) and (protect\$ adj (layer or film)) and (wet adj etch\$6)	US-PGPUB; USPAT	OR	ON	2005/06/07 09:10
S12	2	(polysilicon adj gate adj electrode) with (source and drain) with ((protect\$ or block\$6) adj (layer or film)) with (silicide)	US-PGPUB; USPAT	OR	ON	2005/06/08 10:38
S13	213	(polysilicon adj gate adj electrode) and (source and drain) and ((protect\$ or block\$6) adj (layer or film)) and (silicide)	US-PGPUB; USPAT	OR	ON	2005/06/08 10:50
S18	39	(polysilicon adj gate adj electrode) and (source and drain) and (((protect\$ or block\$6) adj (layer or film)) with (silicide))	US-PGPUB; USPAT	OR	ON	2005/06/08 10:50
S19	13	(polysilicon adj gate adj electrode) and (source and drain) and (((protect\$ or block\$6) adj (layer or film)) near (silicide))	US-PGPUB; USPAT	OR	ON	2005/06/08 10:59
S20	76	(polysilicon adj gate adj electrode) and (source and drain) and (((protect\$ or block\$6) adj (layer or film)) same (silicide))	US-PGPUB; USPAT	OR	ON	2005/06/08 10:50
S21	134	(polysilicon adj gate adj electrode) and (source and drain) and (((protect\$ or block\$6 or mask\$6) adj (layer or film)) same (silicide))	US-PGPUB; USPAT	OR	ON	2005/06/08 10:51
S22	75	(polysilicon adj gate adj electrode) and (source and drain) and (((protect\$ or block\$6 or mask\$6) adj (layer or film)) with (silicide))	US-PGPUB; USPAT	OR	ON	2005/06/08 11:06
S23	55	(polysilicon adj gate adj electrode) and (source and drain) and (((protect\$ or block\$6 or masking) adj (layer or film)) with (silicide))	US-PGPUB; USPAT	OR	ON	2005/06/08 11:03
S24	75	(polysilicon adj gate adj electrode) and (source and drain) and (((protect\$ or block\$6 or mask\$6) adj (layer or film)) with (silicide)) and @ad<="20040326"	US-PGPUB; USPAT	OR	ON	2005/11/17 13:35
S25	8	("6800905") or ("6770516") or ("6768158") or ("6630388") or ("6525403") or ("6432829") or ("6642090") or ("6764884").PN.	USPAT	OR	OFF	2005/06/08 13:33

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S27	75	(polysilicon adj gate adj electrode) and (source and drain) and (((protect\$ or block\$6 or mask\$6) adj (layer or film)) with (silicide)) with (silicid\$6)) and @ad<="20040326"	US-PGPUB; USPAT	OR	ON	2005/06/08 12:26
S28	8	((polysilicon adj gate adj electrode) same (source and drain) same (((protect\$ or block\$6 or mask\$6) adj (layer or film)) with (silicide)) with (silicid\$6))) and @ad<="20040326"	US-PGPUB; USPAT	OR	ON	2005/06/08 12:27
S29	2	((polysilicon adj gate adj electrode) with (source and drain) with (((protect\$ or block\$6 or mask\$6) adj (layer or film)) with (silicide)) with (silicid\$6))) and @ad<="20040326"	US-PGPUB; USPAT	OR	ON	2005/06/10 07:12
S30	75	((polysilicon adj gate adj electrode) and (source and drain) and (((protect\$ or block\$6 or mask\$6) adj (layer or film)) with (silicide)) with (silicid\$6))) and @ad<="20040326"	US-PGPUB; USPAT	OR	ON	2005/06/08 12:27
S31	2	((polysilicon adj gate adj electrode) with (source and drain) with (((protect\$ or block\$6 or mask\$6) adj (layer or film)) with (silicide)) with (silicid\$6 or salicid\$6))) and @ad<="20040326"	US-PGPUB; USPAT	OR	ON	2005/06/08 12:29
S32	8	((polysilicon adj gate adj electrode) same (source and drain) same (((protect\$ or block\$6 or mask\$6) adj (layer or film)) with (silicide)) with (silicid\$6 or salicid\$6))) and @ad<="20040326"	US-PGPUB; USPAT	OR	ON	2005/06/08 12:29
S33	16	("6787854") or ("6642090") or ("6475890") or ("6472258") or ("6475869") or ("20020153587") or ("20020093053") or ("20020130354") or ("20020177263") or ("20030122186") or ("6583469") or ("6413802") or ("6225173") or ("6458662") or ("6300182") or ("5757038").PN.	US-PGPUB; USPAT	OR	OFF	2005/06/08 14:05

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S34	7	(("5462638") or ("5486282") or ("5796168") or ("5620611") or ("5937320") or ("6293457") or ("6468413")).PN.	US-PGPUB; USPAT	OR	OFF	2005/06/08 14:56
S94	1	("6489229").PN.	USPAT	OR	OFF	2005/06/10 07:24
S10 1	7	(("20050121748") or ("5323032") or ("5665616") or ("5599723")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/10 06:51
S10 3	2	(((polysilicon adj gate adj electrode) and (source and drain)) with (((protect\$ or block\$6 or mask\$6) adj (layer or film)) with (silicide)) with (silicid\$6 or salicid\$6)) and @ad<="20040326"	US-PGPUB; USPAT	OR	ON	2005/06/10 07:16
S10 4	15	(((polysilicon adj gate adj electrode) and (source and drain)) with ((silicid\$6 or salicid\$6) adj gate)) and @ad<="20040326"	US-PGPUB; USPAT	OR	ON	2005/06/10 07:21
S10 5	99	(438/583).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/10 07:22
S10 6	1232	(438/592).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/10 07:23
S10 7	485	(438/649).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/10 07:23
S10 8	132	(438/651).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/10 07:23
S10 9	1	("6140210").PN.	USPAT	OR	OFF	2005/06/10 07:24

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S11 0	1	("20050215037").PN.	US-PGPUB	OR	OFF	2005/11/03 14:34
S11 1	7113	((gate or electrode) with (silicid\$4 or salicid\$4)) and ((source and drain) with (silicide))	US-PGPUB; USPAT	OR	ON	2005/11/03 14:37
S11 2	6910	((gate) with (silicid\$4 or salicid\$4)) and ((source and drain) with (silicide))	US-PGPUB; USPAT	OR	ON	2005/11/03 14:37
S11 3	6889	((gate) with (silicid\$4 or salicid\$4)) and ((source same drain) with (silicide))	US-PGPUB; USPAT	OR	ON	2005/11/03 14:37
S11 4	6185	((gate) with (silicid\$4 or salicid\$4)) and ((source near drain) with (silicide))	US-PGPUB; USPAT	OR	ON	2005/11/03 14:38
S11 5	4891	(((gate) with (silicid\$4 or salicid\$4)) and ((source near drain) with (silicide))) and polysilicon	US-PGPUB; USPAT	OR	ON	2005/11/03 14:41
S11 6	849	(((gate) with (silicid\$4 or salicid\$4)) and ((source near drain) with (silicide))) and (silicid\$4 adj gate)	US-PGPUB; USPAT	OR	ON	2005/11/04 08:58
S11 7	592	(((gate) with (silicid\$4 or salicid\$4)) and ((source near drain) with (silicide))) and (silicid\$4 adj gate)	USPAT	OR	ON	2005/11/04 08:32
S11 8	257	(((gate) with (silicid\$4 or salicid\$4)) and ((source near drain) with (silicide))) and (silicid\$4 adj gate)	US-PGPUB	OR	ON	2005/11/04 08:58
S12 1	6	("6821887") or ("6555453") or ("6096609").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/17 13:20
S12 2	9	(polysilicon adj gate adj electrode) and (source and drain) and (((protect\$ or block\$6 or mask\$6) adj (layer or film)) with (silicide)) and @ad<="20040326" and (cobalt adj silicide) and (nickel adj silicide)	US-PGPUB; USPAT	OR	ON	2006/05/02 18:50

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S12 8	4	(polysilicon adj gate) and (source and drain) and (((protect\$ or block\$6 or mask\$6) adj (layer or film)) near (silicide)) and (silicid\$4 or salicid\$4) and @ad<="20040326" and (cobalt adj silicide) and (nickel adj silicide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/02 18:56
S12 9	208	(polysilicon adj gate) and (source and drain) and (silicide adj (layer or film)) and (silicid\$4 or salicid\$4) and @ad<="20040326" and (cobalt adj silicide) and (nickel adj silicide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/03 10:20
S13 1	2585	(gate or (gate adj electrode)) near silicide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/03 10:19
S13 2	2306	(gate) near silicide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/03 10:19
S13 3	26	(polysilicon adj gate) and (source and drain) and (silicide adj (layer or film)) and ((silicid\$4 or salicid\$4) adj (polysilicon adj gate)) and @ad<="20040326" and (cobalt adj silicide) and (nickel adj silicide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/03 10:21
S13 4	165	(polysilicon adj gate) and (source and drain) and (silicide adj (layer or film)) and ((silicid\$4 or salicid\$4) adj (polysilicon adj gate)) and @ad<="20040326"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/03 10:21
S13 5	2	("6514859") or ("6562718").PN.	USPAT	OR	OFF	2006/05/11 08:43
S13 6	4	("20050215055") or ("6,864,178") or ("6,620,718") or ("6,830,987").PN.	US-PGPUB; USPAT	OR	OFF	2006/05/11 09:45
S13 7	6	("20050215055") or ("6,864,178") or ("6,620,718") or ("6,830,987") or ("6514859") or ("6562718").PN.	US-PGPUB; USPAT	OR	OFF	2006/05/11 09:45